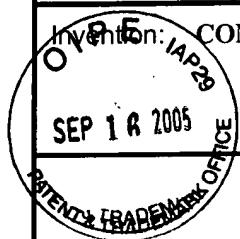


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INVENTION: COMPOSITION FOR ANTIREFLECTIVE COATING AND METHOD FOR FORMING SAME

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(54) ANTIREFLECTION COMPOSITION AND RESIST PATTERN FORMING
METHOD

(57)Abstract:

PROBLEM TO BE SOLVED: To suppress mixing with a photoresist, to ensure satisfactory step coverage even with a thin film thickness, to prevent dissolution at the time of developing a photoresist film, to attain high absorbance even when the amt. of a light absorber added is small and to ensure satisfactory dry etching resistance by incorporating water and PVA and imparting acidity of a specified pH or below.

SOLUTION: This compsn. contains water and PVA and has \leq pH4. The PVA resin is produced by hydrolyzing polyvinyl acetate and converting acetyl groups in the polyvinyl acetate into hydroxyl groups. The mol% of such hydroxyl groups means the degree of saponification and PVA resin having 70-99% degree of saponification is preferably used. In the case of <70% degree of saponification, developer resistance is deteriorated at the time of development and mixing is liable to occur at the time of forming a photoresist film. In the case of >99%, the shelf stability of this compsn. is deteriorated.

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